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PCT/KR2003/001394

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INTERNATIONAL PRELIMINARY EXAMINATION REPORT

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(PCT Artcle 36 and Rule 70)

Applicant's or agent's file reference PCA30539/IPN	FOR FURTHER ACTION S	eeNotificationofTransmittalofInte	rnationalPreliminary EA/416)	
International application No. PCT/KR2003/001391	International filing date(day/month/year) 14 JULY 2003 (14.07.2003) Priority date (day/month/year) 17 DECEMBER 200		nth/year)	
International Patent Classification (IPC) IPC7 H01L 21/205	or national classification and IPC			
Applicant IBULE PHOTONICS INC. et	al			
and is transmitted to the applicar 2. This REPORT consists of a total This report is also accompamended and are the basis 70.16 and Section 607 of t	of sheets, including anied by ANNEXES, i.e., sheets of for this report and/or sheets contain the Administrative Instructions under	g this cover sheet. the description, claims and/or drawing rectifications made before the	wings which have been	
These annexes consist of a total				
3. This report contains indications relating to the following items: I				
Date of submission of the demand 15 JULY 2004 (1		completion of this report 22 MARCH 2005 (22.03.2005)	5)	
Name and mailing address of the IPE Korean Intellectual Prop 920 Dunsan-dong, Seo-g Republic of Korea Facsimile No. 82-42-472-7140	erty Office u, Daejeon 302-701,	rized officer LEE, Yoon Jik none No. 82-42-481-5731		

INTERNATIONAL PRELIMINARY EXAMINATION REPORT

International aplication No.

PCT/KR2003/001391

I. Ba	sis of the report		
1. Wi	h regard to the elements of the international application:*		
\boxtimes	the international application as originally filed		
	the description:		
	pages	, as originally filed	
	pages, filed with the letter of	, filed with the demand	
-	1 the claims:	 	
│ └	pages	, as originally filed	
	pages, as amended (together with an	y statment) under Article 19	
	pages, filed with the letter of	, filed with the demand	
			
ᆫ	the drawings:	·	
	pagespages	, as originally filed , filed with the demand	
	pages, filed with the letter of	,	
	the sequence listing part of the description:		
	pages	, as originally filed	
	pages, filed with the letter of	, filed with the demand	
. <i>.</i>	pages, med with the following		
th	ith regard to the language, all the elements marked above were available or furnished to this Aut e international application was filed, unless otherwise indicated under this item. hese elements were available or furnished to this Authority in the following language		
	<u> </u>	• which is	
<u> </u>	the language of a translation furnished for the purposes of international search (under Rule 2	3.1(b)).	
! ∟	the language of publication of the international application (under Rule 48.3(b)).		
	the language of the translation furnished for the purposes of international preliminary examor 55.3).	nination(under Rules 55.2 and/	
	With regard to any nucleotide and/or amino acid sequence disclosed in the international appropriate reliminary examination was carried out on the basis of the sequence listing:	lication, the international	
Г	contained inthe international application in written form.	•	
	filed together with the international application in computer readable form.		
Ιг	furnished subsequently to this Authority in written form.		
l F	furnished subsequently to this Authority in computer readable form		
-	The statement that the subsequently furnished written sequence listing does not go b	eyond the disc losure in the	
-	international applicationas as filed has been furinshed.	-	
E	The statement that the information recorded in computer readable form is identical to the written sequence listing has been furnished.		
4. [The amendments have resulted in the cancellation of:		
• -	the description, pages	,	
1	the claims, Nos.		
	the drawings, sheets		
5.			
	This report has been established as if (some of) the amendments had not been made, sing go beyond the disclosure as filed, as indicated in the Supplemental Box(Rule 70.2(c)).**	nce they have been considered to	
in	placement sheets which have been furnished to the receiving Office in response to an invitation to this opinion as "originally filed." and are not annexed to this report since they do not contain In 170.17).	ınder Article 14 are referred to n amendments (Rules 70.16	
** A	** Any replacement sheet containing such amendments must be referred to under item I and annexed to this report.		

INTERNATIONAL PRELIMINARY EXAMINATION

International aplication No. PCT/KR2003/001391

V. Reasoned statement unde	er Article 35(2) with regard to novelty, ir	eventive step or industrial applicability:
citations and explanation	ns supporting such statement	

1.	Statement	•		
	Novelty (N)	Claims	1-16	YES
		Claims		No
	Inventive step (IS)	Claims	1-16	YES
		Claims		NO
	Industrial applicability (IA)	Claims	1-16	YES
		Claims		NO

2. Citations and explanations (Rule 70.7)

Reference is made to the following documents from the International Search Report (ISR).

D1: JP 12-068455 A
D2: JP 09-186376 A
D3: US 6054331 B
D4: KR 1998-80778 A
D5: JP 08-253324 A
D6: JP 13-107238 A
D7: JP 08-186182 A
D8: US 5650362 B

D9: US 6498097 B D10: EP 0390139 A2

D1 discloses a method for obtaining a high dielectric constant capacitor, which comprises a thermal oxide film formed on the surface of a Si single-crystal (111) plane substrate, a Ta film formed thereon as an adhesive layer, a Ti-doped WN film formed via the adhesive layer as a lower electrode layer of a ferroelectric capacitor, a ferroelectric thin film PZT formed thereon, and a Ti-doped WN film formed on the ferroelectric thin film as an upper layer of the ferroelectric capacitor.

D2 discloses a thin film of ferroelectric crystal containing Bi, Ti and O as constitutive elements which can attain a high residual spontaneous polarization by shifting the compositional ratio of Bi/Ti from stoichiometric composition.

D3 discloses an apparatus and methods of depositing a platinum film which is used as a bottom electrode for a capacitor in a DRAM cell or a non-volatile ferroelectric memory cell. The platinum film is formed in two separate processes, wherein a first thickness platinum part thereof is deposited under an inert gas atmosphere, and the second thickness platinum part is deposited under an atmosphere containing oxygen, nitrogen and/or a mixture thereof as well as an inert gas. The platinum film is annealed under a vacuum atmosphere to remove the oxygen and/or nitrogen introduced during the deposition of the second thickness platinum part.

D4 discloses a manufacturing method of a high-quality SOI wafer which is excellent in controllability, productivity and economics.

D5 discloses a ferroelectric thin-film constitution body which is obtained by forming an oxide thin film of a Bi-based layer perovskite type crystal structure on a substrate so as to properly arrange the (c)-axis of the crystal axis in the direction perpendicular to the substrate surface and further forming a ferroelectric thin film having the perovskite type crystal structure represented by the general formula ABO₃ on the resultant oxide thin film.

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Supplemental Box

(To be used when the space in any of the preceding boxes is not sufficient)

Continuation of:

Box V

D6 discloses a method for forming a ferroelectric film for a ferroelectric device for integrated circuit which embraces steps of: (a) forming a first lower electrode layer of platinum (Pt) having a first fit crystal lattice structure; and (b) forming a single phase Perovskite ferroelectric film which has a second crystal lattice structure practically identical with the first fit crystal lattice structure and is formed on the first lower electrode layer.

D7 discloses a ferroelectric thin film grown by the multidimensional ECR sputtering on a Pt thin film.

D8 discloses an oriented conductive thin film useful as a thin film electrode or a thin film resistor which may be made by coating a single crystal substrate with a metal oxide precursor solution containing an organometallic compound, and subjecting the coating layer to thermal decomposition, followed by annealing the coated substrate.

D9 discloses a platinum film orientation-controlled to (111), (200) and/or (220) which is provided by depositing the platinum film under an atmosphere containing an oxygen component.

D10 discloses a ferroelectric thin film consisting of a single crystal which has the perovskite structure.

Claims 1 to 16 of the present invention relate to a ferroelectric single crystal film structure and its preparing method, which comprises the steps of: forming a layer of a material having a perovskite crystal structure on a substrate as an electrode layer, and growing a layer of a ferroelectric single crystal on the electrode material layer by a pulsed laser deposition (PLD) or metallorganic chemical vapor deposition (MOGVD) method.

Document D1-D7, D9 and D10 do not disclose a electrode layer having a perovskite crystal structure. Document D5 and D8 disclose a electrode layer having a perovskite crystal structure, but does not disclose a ferroelectric 'single crystal' structure formed by a pulsed laser deposition. Therefore the novelty and the inventive step of the subject matter of the claims 1-16 is acknowledged.

The industrial applicability of the subject matter claimed in claims 1-13 is self-evident.